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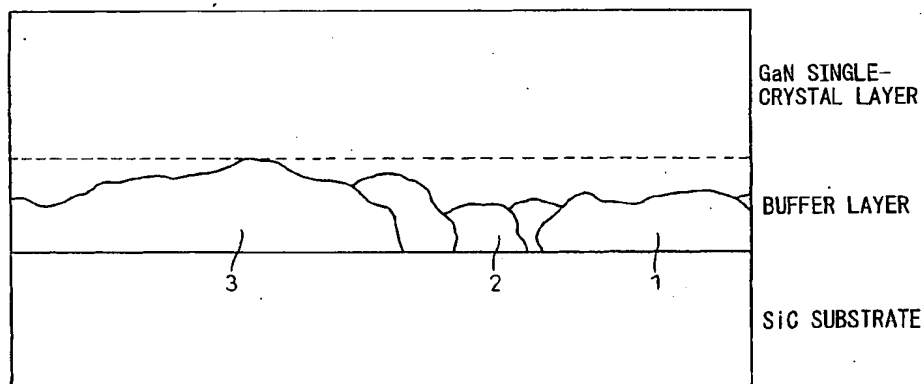
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(54) Title: **GROUP III NITRIDE SEMICONDUCTOR MULTILAYER STRUCTURE**



(57) Abstract: An object of the present invention is to provide a Group III nitride semiconductor multilayer structure having a smooth surface and exhibiting excellent crystallinity, which multilayer structure employs a low-cost substrate that can be easily processed. Another object is to provide a Group III nitride semiconductor light-emitting device comprising the multilayer structure. The inventive Group III nitride semiconductor multilayer structure comprises a substrate; an $\text{Al}_x\text{Ga}_{1-x}\text{N}$ ($0 \leq x \leq 1$) buffer layer which is provided on the substrate and has a columnar or island-like crystal structure; and an $\text{Al}_y\text{In}_z\text{Ga}_{1-x-y}\text{N}$ ($0 \leq x \leq 1$, $0 \leq y \leq 1$, $0 \leq x + y \leq 1$) single-crystal layer provided on the buffer layer, wherein the substrate has, on its surface, non-periodically distributed grooves having an average depth of 0.01 to 5 μm .

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